

IN THE CLAIMS:

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1. (Currently Amended) A device for a projection exposure system, (there being arranged in the beam path) of the pulsed laser light source at least one beam splitter apparatus by means of which (whereby) at least one detour line for at least one partial beam is produced via reflecting components, with an easily detuned Kepler telescope arranged in the detour line wherein there is arranged in the beam path a beam recombining element in or on which the partial beams are reunited to form a total beam; said beam splitter apparatus having a mirror which is arranged at an angle to the beam path.
No Detraction

2. (Previously Amended) The device as claimed in claim 1, wherein the detour line has a length such that an optical path difference of more than 0.5 m is produced between the partial beams.

3. (Previously Amended) The device as claimed in claim 1, wherein at least three reflecting components form a detour line .

~~4.~~ (Canceled)

5. (Original) The device as claimed in claim 4, wherein the angle is between 35 and 50°.

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6. (Original) The device as claimed in claim 5, wherein the Brewster angle is provided as the angle.

7. (Previously Amended) The device as claimed in claim 1, wherein the reflecting components are constructed as mirrors.

8. (Previously Amended) The device as claimed in claim 1, wherein two detour lines are arranged in series in the beam path .

9. (Previously Amended) The device as claimed in claim 8, wherein a first detour line has a length of over 2 m, and a second detour line has a length of over 10 m.

~~10.~~ (Canceled)

11. (Previously Amended) The device as claimed in claim 1, wherein the beam recombining element is constructed such that a portion of the partial beam which has run via the detour line is repeatedly sent via the detour line.

12. (Previously Amended) The device as claimed in claim 11, wherein at least one phase—retarding plate is arranged in the beam path.

13. (Previously Amended) The device as claimed in claim 12, wherein a 10 phase-retarding plate is arranged in the beam path upstream of the beam splitter apparatus, and at least one further phase—retarding plate is arranged in the detour line.

14. (New) A device for a projection exposure system, there being arranged in the beam path of the pulsed laser light source at least one beam splitter apparatus whereby at least one detour line for at least one partial beam is produced via reflecting components, with an easily detuned Kepler telescope arranged in the detour line wherein there is arranged in the beam path a beam recombining element in or on which the partial beams are reunited to form a total beam, said beam splitter apparatus being arranged at the Brewster angle to the beam path.

15. (New) A device for a projection exposure system, there being arranged in the beam path of the pulsed laser light source at least one beam splitter apparatus whereby at least one detour line for at least one partial beam is produced via reflecting components, with an easily detuned Kepler telescope arranged in the detour line wherein there is arranged in the beam path a beam recombining element in or on which the partial beams are reunited to form a total beam, said beam splitter apparatus being arranged at an angle between 35 and 50 degrees to the beam path.